

Special Issue

Development and Application of High Sensitivity Instrumentation

Message from the Guest Editor

The development of highly sensitive instruments is a crucial issue in various fields. First of all, it is certainly fundamental in the fields of devices and materials characterization, DC charge transport investigations, high-temperature superconductor characterizations, and precise thermoelectric power measurements. Over time, highly sensitive instrumentation has also gained importance in more modern applications, such as sensors, biomedical applications, environmental monitoring, and sport. The purpose of this Special Issue is to collect contributions covering the state of the art and future prospects in this field. Papers focused on the applicative aspects of the instrumentation and on the circuit design are welcome.

Guest Editor

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Deadline for manuscript submissions

closed (20 November 2022)



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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal *Applied Sciences* has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

Editor-in-Chief

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